

operations include, but are not limited to, crystal growing; solvent stations used to prepare and clean materials for subsequent processing or for parts cleaning; wet chemical stations used for cleaning (other than solvent cleaning); photoresist application, developing, and stripping; etching; gaseous operation stations used for stripping, cleaning, doping, etching, and layering; separation; encapsulation; and testing. Research and development operations associated with semiconductor manufacturing and conducted at a

semiconductor manufacturing facility are considered to be semiconductor manufacturing process units.

Storage tank means a stationary unit that is constructed primarily from nonearthen materials (such as wood, concrete, steel, fiberglass, or plastic) which provides structural support and is designed to hold an accumulation of liquids or other materials used in or generated by a semiconductor manufacturing process unit. The following are not storage tanks for the purposes of this subpart:

(1) Tanks permanently attached to motor vehicles such as trucks, railcars, barges, or ships;

(2) Flow-through tanks where wastewater undergoes treatment (such as pH adjustment) before discharge, and are not used to accumulate wastewater;

(3) Bottoms receiver tanks; and

(4) Surge control tanks.

Tables to Subpart BBBBB of Part 63

As stated in § 63.7187, you must comply with the requirements for performance tests in the following table:

TABLE 1 TO SUBPART BBBBB OF PART 63.—REQUIREMENTS FOR PERFORMANCE TESTS

For . . .	You must . . .	Using . . .	According to the following requirements . . .
1. Process or storage tank vent streams.	<p>a. Select sampling port's location and the number of traverse ports.</p> <p>b. Determine velocity and volumetric flow rate.</p> <p>c. Conduct gas molecular weight analysis.</p> <p>d. Measure moisture content of the stack gas.</p>	<p>Method 1 or 1A of 40 CFR part 60, appendix A.</p> <p>Method 2, 2A, 2C, 2D, 2F, or 2G of 40 CFR part 60, appendix A.</p> <p>i. Method 3, 3A, or 3B of 40 CFR part 60, appendix A.</p> <p>ii. ASME PTC 19.10–1981–Part 10.</p> <p>Method 4 of 40 CFR part 60, appendix A.</p>	<p>Sampling sites must be located at the inlet (if emission reduction or destruction efficiency testing is required) and outlet of the control device and prior to any releases to the atmosphere.</p> <p>For HAP reduction efficiency testing only; not necessary for determining compliance with a ppmv concentration limit.</p> <p>For flow rate determination only.</p> <p>You may use ASME PTC 19.10–1981–Part 10 (available for purchase from Three Park Avenue, New York, NY 10016–5990) as an alternative to EPA Method 3B.</p> <p>For flow rate determination and correction to dry basis, if necessary.</p>
2. Process vent stream	<p>a. Measure organic and inorganic HAP concentration (two method option).</p> <p>c. Measure organic and inorganic HAP simultaneously (one method option).</p>	<p>i. Method 18, 25, or 25A of 40 CFR part 60, appendix A, AND</p> <p>ii. Method 26 or 26A of 40 CFR part 60, appendix A.</p> <p>Method 320 of 40 CFR part 63, appendix A.</p>	<p>(1) To determine compliance with the percent by weight emission reduction limit, conduct simultaneous sampling at inlet and outlet of control device and analyze for same organic and inorganic HAP at both inlet and outlet; and</p> <p>(2) If you use Method 25A to determine the TOC concentration for compliance with the 20 ppmv emission limitation, the instrument must be calibrated on methane or the predominant HAP. If you calibrate on the predominant HAP, you must comply with each of the following:</p> <p>—The organic HAP used as the calibration gas must be the single organic HAP representing the largest percent of emissions by volume.</p> <p>—The results are acceptable if the response from the high level calibration gas is at least 20 times the standard deviation of the response from the zero calibration gas when the instrument is zeroed on its most sensitive scale.</p> <p>—The span value of the analyzer must be less than 100 ppmv.</p> <p>To determine compliance with 98 percent reduction limit, conduct simultaneous sampling at inlet and outlet of control device and analyze for same organic and inorganic HAP at both inlet and outlet.</p> <p>To determine compliance with the percent by weight emission reduction limit, conduct simultaneous sampling at inlet and outlet of control device and analyze for same organic and inorganic HAP at both inlet and outlet.</p>
3. Storage tank vent stream	Measure inorganic HAP concentration.	Method 26 or 26A of 40 CFR part 60, appendix A, or Method 320 of 40 CFR part 63, appendix A.	To determine compliance with percent by weight emission reduction limit, conduct simultaneous sampling at inlet and outlet of control device and analyze for same inorganic HAP at both inlet and outlet.

As stated in § 63.7193, you must comply with the applicable General Provisions requirements according to the following table: